

In the Claims:

1. **(currently amended)** A process for the production of a strongly adherent metal coating on ~~an inorganic or organic~~ a glass, ceramic or polymeric substrate, wherein
  - a) a low temperature plasma treatment, a corona discharge treatment or a flame treatment is carried out on the ~~inorganic or organic~~ glass, ceramic or polymeric substrate,
  - b) one or more photoinitiators or mixtures of photoinitiators with monomers or/and oligomers, containing at least one ethylenically unsaturated group, or solutions, suspensions or emulsions of the afore-mentioned substances, are applied to the inorganic or organic substrate to produce a layer which is optionally dried,
  - c) irradiating the layer of step b) is optionally dried and is irradiated with electromagnetic waves; with from 1 to 1000 mJ /cm<sup>2</sup> of UV/Vis light having wavelengths from 150 to 700 nm to fix the one or more photoinitiators in the layer of step b); and, after said irradiation,
  - d) on the substrate so precoated with photoinitiator a metal, half-metal or metal oxide is deposited from the gas phasewherein a coated substrate comprising a glass, ceramic or polymeric substrate affixed to the irradiated layer of step b), which layer of step b) is affixed to a deposited metal, half-metal or metal oxide layer is obtained.
2. **(currently amended)** A process according to claim 1, wherein in step d) an irradiation with electromagnetic waves is carried out, either while depositing the metal, half-metal or metal oxide from the gasphase or after the deposition.
3. **(original)** A process according to claim 1, wherein the photoinitiator is a compound or combination of compounds from the classes of benzoines, benzil ketals, acetophenones, hydroxyalkylphenones, aminoalkylphenones, acylphosphine oxides, acylphosphine sulfides, acyloxyiminoketones, peroxy compounds, halogenated acetophenones, phenylglyoxylates, dimeric phenylglyoxalates, benzophenones, oximes and oxime esters, thioxanthenes, thiazolines, ferrocenes, coumarins, dinitrile compounds, titanocenes, sulfonium salts, iodonium salts, diazonium salts, onium salts, borates, triazines, bisimidazoles, polysilanes and dyes, and also corresponding coinitiators and/or sensitisers.

4. **(original)** A process according to claim 1, wherein the photoinitiator is a compound of formula I or Ia



wherein

**(IN)** is a photoinitiator base structure;

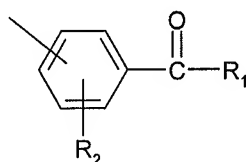
**A** is a spacer group or a single bond;

**(RG)** is hydrogen or at least one functional ethylenically unsaturated group; and

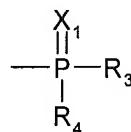
**(RG')** is a single bond or a divalent radical that contains at least one functional ethylenically unsaturated group, or is a trivalent radical.

5. **(original)** A process according to claim 4, wherein in the compound of formula I or Ia

**(IN)** is a photoinitiator base structure of formula (II) or (III)

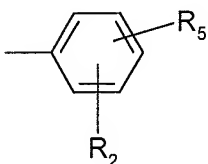


(II),



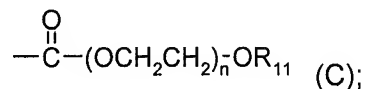
(III),

**R<sub>1</sub>** is a group (A), (B), (C) or (III)



(A),

**-CR<sub>6</sub>R<sub>7</sub>R<sub>8</sub>** (B)



(C);

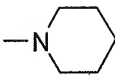
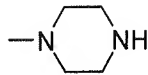
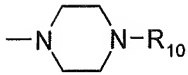
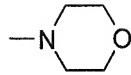
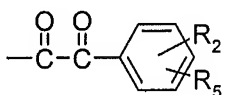
**n** is a number from 0 to 6;

**R<sub>2</sub>** is hydrogen, C<sub>1</sub>-C<sub>12</sub>alkyl, halogen, the group (RG)-A- or, when **R<sub>1</sub>** is a group (A), two radicals

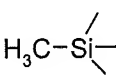
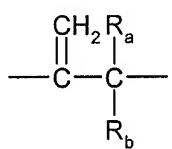
**R<sub>2</sub>** in the ortho-position to the carbonyl group may also together be -S- or ;

**R<sub>3</sub>** and **R<sub>4</sub>** are each independently of the other C<sub>1</sub>-C<sub>6</sub>alkyl, C<sub>1</sub>-C<sub>6</sub>alkanoyl, phenyl or benzoyl, the radicals phenyl and benzoyl each being unsubstituted or substituted by halogen, C<sub>1</sub>-C<sub>6</sub>alkyl, C<sub>1</sub>-C<sub>6</sub>alkylthio or by C<sub>1</sub>-C<sub>6</sub>alkoxy;

**R<sub>5</sub>** is hydrogen, halogen, C<sub>1</sub>-C<sub>12</sub>alkyl or C<sub>1</sub>-C<sub>12</sub>alkoxy or the group (RG)-A- ;

$R_6$  is  $OR_9$  or  $N(R_9)_2$  or is , , ,  or  $SO_2R_9$ ;  
 $R_7$  and  $R_8$  are each independently of the other hydrogen,  $C_1$ - $C_{12}$ alkyl,  $C_2$ - $C_{12}$ alkenyl,  $C_1$ - $C_{12}$ alkoxy, phenyl or benzyl or  $R_7$  and  $R_8$  together are  $C_2$ - $C_6$ alkylene;  
 $R_9$  is hydrogen,  $C_1$ - $C_6$ alkyl or  $C_1$ - $C_6$ alkanoyl;  
 $R_{10}$  is hydrogen,  $C_1$ - $C_{12}$ alkyl or phenyl;  
 $R_{11}$  is  $C_1$ - $C_4$ alkyl or ; and  
 $X_1$  is oxygen or sulfur.

6. **(previously presented)** A process according to claim 5, wherein in the compound of formula I or Ia  
 (RG) is  $R_cR_bC=CR_a$ ;

(RG') is  or , and

$R_a$ ,  $R_b$  and  $R_c$  are each independently of the other hydrogen or  $C_1$ - $C_6$ alkyl.

7. **(previously presented)** A process according to claim 1, wherein the photoinitiator(s) or mixtures thereof with monomers or oligomers are used in combination with one or more liquids in the form of solutions, suspensions and emulsions.

8. **(previously presented)** A process according to claim 1, wherein an inert gas or a mixture of inert gas with reactive gas is used as the plasma gas.

9. **(original)** A process according to claim 8, wherein air,  $H_2$ ,  $CO_2$ , He, Ar, Kr, Xe,  $N_2$ ,  $O_2$  or  $H_2O$  are used singly or in the form of a mixture.

10. **(previously presented)** A process according to claim 1, wherein the photoinitiator layer applied has a layer thickness of up to 500 nm.

11. **(original)** A process according to claim 1, wherein process step b) is carried out immediately after process step a) or within 24 hours after process step a).

12. **(previously presented)** A process according to claim 1, wherein the concentration of photo-initiator or photoinitiators in process step b) is from 0.01 to 99.5 %.

13. **(original)** A process according to claim 1, wherein process step c) is carried out immediately after process step b) or within 24 hours after process step b).

14. **(original)** A process according to claim 1, wherein drying in process step c) is effected in ovens, with hot gases, heated rollers or IR or microwave radiators or by absorption.

15. **(previously presented)** A process according to claim 1, wherein irradiation in process step c) and/or d) is effected with a source that emits electromagnetic waves of wavelengths in the range from 200 nm to 700 nm, or by electron beams.

16-18. **(cancelled)**

19. **(withdrawn)** A strongly adherent coating obtained by a process according to claim 1.

20. **(withdrawn)** A strongly adherent coating obtained by a process according to claim 2.

21. **(previously presented)** A process according to claim 2, wherein an inert gas or a mixture of inert gas with reactive gas is used as the plasma gas.